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PATENT
Customer No. 22,852
Attorney Docket No. 3180.0344

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:)
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HITOSHI ITO)
)
)
Application No.: 10/725,570) Group Art Unit: 1756
)
)
Filed: December 3, 2003) Examiner: Unknown
)
For: PHOTOMASK, METHOD FOR) Confirmation No.: 5142
 FABRICATING A PATTERN AND)
 METHOD FOR MANUFACTURING)
 A SEMICONDUCTOR DEVICE)

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. § 1.97(b)

Pursuant to 37 C.F.R. §§ 1.56 and 1.97(b), applicant brings to the attention of the Examiner the documents on the attached listing. This Information Disclosure Statement is being filed before the mailing date of a first Office Action on the merits for the above-referenced application.

Copies of the listed foreign and non-patent literature documents are attached.

Applicant respectfully requests that the Examiner consider the listed documents and indicate that they were considered by making appropriate notations on the attached form.

The following is a concise statement of relevance of the non-English language documents.

1. Japanese Publication No. 10-223634 is discussed on page 3 of the above-identified application. In addition, an English-language abstract is attached.

2. Japanese Publication No. 7-74175 is discussed on page 3 of the above-identified application. In addition, an English-language abstract is attached.

This submission does not represent that a search has been made or that no better art exists and does not constitute an admission that each or all of the listed documents are material or constitute "prior art." If the Examiner applies any of the documents as prior art against any claim in the application and applicant determines that the cited documents do not constitute "prior art" under United States law, applicant reserves the right to present to the office the relevant facts and law regarding the appropriate status of such documents.

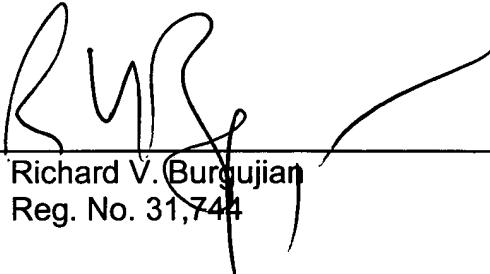
Applicant further reserves the right to take appropriate action to establish the patentability of the disclosed invention over the listed documents, should one or more of the documents be applied against the claims of the present application.

If there is any fee due in connection with the filing of this Statement, please charge the fee to our Deposit Account No. 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,
GARRETT & DUNNER, L.L.P.

Dated: 11/3/04

By: 
Richard V. Burgujian
Reg. No. 31,744

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use as many sheets as necessary)

Sheet

1

of

1

Complete if Known

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|-------------------------------|------------------|
| <i>Application Number</i> | 10/725,570 |
| <i>Filing Date</i> | December 3, 2003 |
| <i>First Named Inventor</i> | Hitoshi Ito |
| <i>Art Unit</i> | 1756 |
| <i>Examiner Name</i> | Unknown |
| <i>Attorney Docket Number</i> | 3180.0344 |

U.S. PATENTS AND PUBLISHED U.S. PATENT APPLICATIONS

Note: Copies of the U.S. Patent Documents are not Required in IDS filed after October 21, 2004

FOREIGN PATENT DOCUMENTS

| Examiner Initials | Cite No. ¹ | Foreign Patent Document | Publication Date MM-DD-YYYY | Name of Patentee or Applicant of Cited Document | Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear | Translation ⁶ |
|-------------------|-----------------------|---------------------------------------------------------------------------------|--------------------------------|----------------------------------------------------|------------------------------------------------------------------------------------|--------------------------|
| | | Country Code ³ Number ⁴ Kind Code ⁵ (if known) | | | | |
| | | 10-223634 | 8/21/98 | Japan | | Abstract |
| | | 7-74175 | 3/17/95 | Japan | | Abstract |
| | | | | | | |
| | | | | | | |

NON PATENT LITERATURE DOCUMENTS

| Examiner Initials | Cite No. ¹ | Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published. | Translation ⁶ |
|-------------------|-----------------------|-----------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------------|--------------------------|
| | | INOUE ET AL., "Level-Specific Strategy of KrF Microlithography for 130 nm DRAMs," IEEE (1999), pp. 809-812 | |
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| Examiner Signature | | Date Considered | |
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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.